

Signal Integrity

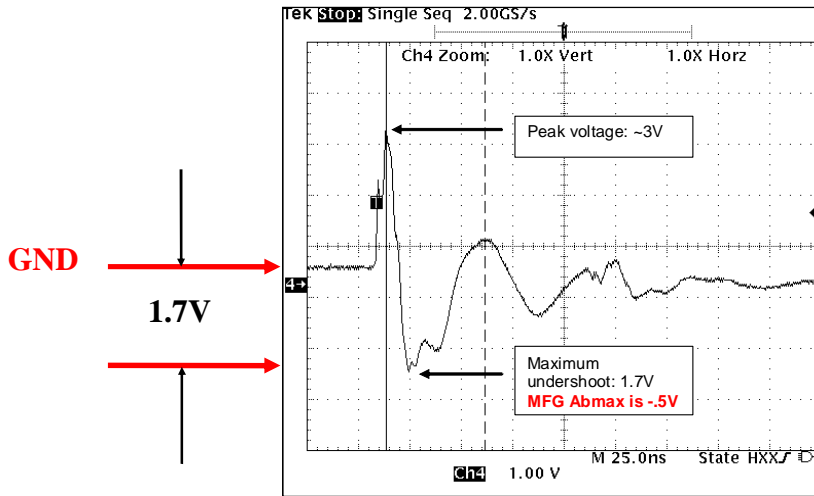
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Nanoroute: What is Signal and Power Integrity?

- **Signal Integrity ensures signals are of sufficient quality to reliably transmit their required information, and do not cause problems to themselves or to other components in the system.**
- **Signal Integrity applies to Digital, Analog and Power electronics**
- **Signal Integrity issues are more common now because electronics are more dense and chips have faster rise times**
 - **Assuring Signal Integrity now involves more knowledge of such RF techniques as terminations, impedance matching**
- **Major function of engineering, next to conceiving the correct design, is implementing the design correctly**
- **Signal integrity assures the circuit design operates as intended and must be designed in.**
 - **Correct design relies on experience, best practices, analysis and simulation to ensure desired signal quality.**

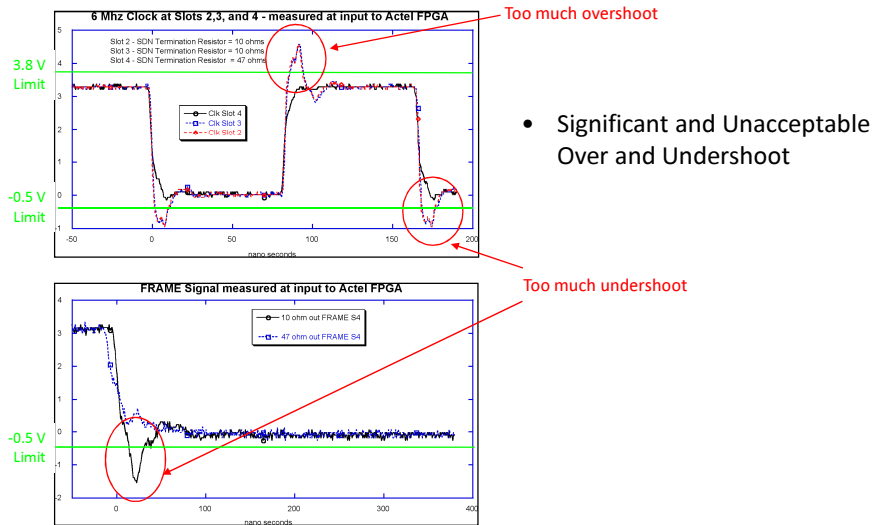
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What is Signal and Power Integrity? (cont.)



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What is Signal and Power Integrity? (cont.)



- Significant and Unacceptable Over and Undershoot

From: Ed James, GSFC, ACE Signal Integrity Tuning

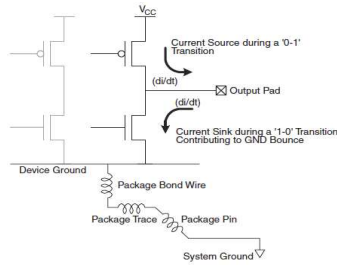
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What is Signal and Power Integrity? (cont.)

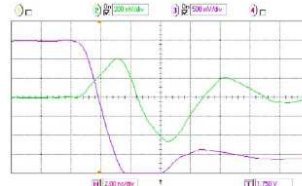
Table 1 • SSO around a Quiet Output for SX-A, RT54SX-S, A500K, and ProASICPLUS Devices

I/O Voltage Compliance SSO	SSO	
	At High Slew	At Low Slew
SX-ART5X-S 5.0V	24**	>40**
SX-ART5X-S 3.3V	32**	>40**
ProASICPLUS 3.3V	32**	>40**
A500 3.3V	32**	>40**

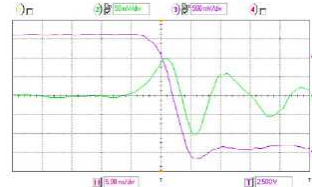
- Notes:
1. *The observed ground bounce is less than 1.5V with a pulse width of less than 2.0ns
 2. **The observed ground bounce is less than 1.25V with a pulse width of less than 2.0ns



- Is 1.5 or 1.25 volts of ground bounce OK?
- 1.5 volts almost 1/2 way between a logic "0" and "1" for 3.3 volt logic



- High Slew
- Tfall = 1.5 ns
 - Gnd Bounce = 0.4V

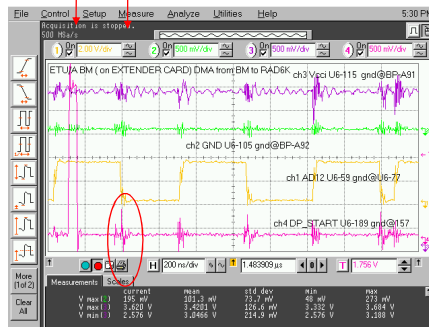


- Low Slew
- Tfall = 6 ns
 - Gnd Bounce = 0.1V

See: Actel SSO Signal Integrity, PDF, Simultaneously Switching Noise and Signal Integrity

What is Signal and Power Integrity? (cont.)

- 1) Valid "Start" Cycle Pulse (Red)
- 2) When Data Bits drive low (Yellow), ground bounces causing a phantom positive glitch on "Start" locking up the system



- Is every thing ok because the ambient "Functional Test" passed?

Purple - 3.3 V
0.5 V/div
Note more noise as AD driven "High"

Green - D Gnd
0.5 V/div
Note more noise as AD driven "Low"

Yellow - AD 12
2 V/div

Red - Start signal
0.5 V/div
Note signal is nominally driven "low", glitches represent internal chip ground

Designing the System Correctly

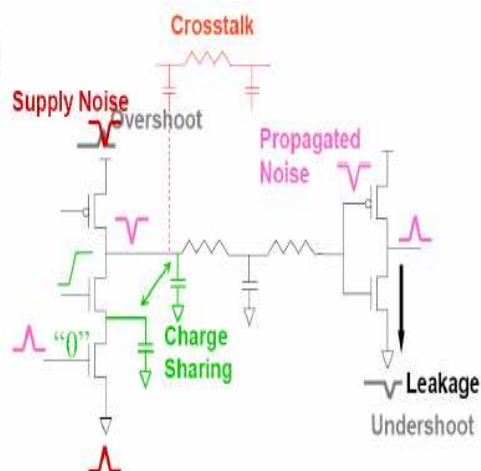
- Fundamentally, signal integrity must be designed in and not "discovered" by test.
 - Tests verify that signals have the intended integrity.
 - Tests are not designed to qualify a poor design
- Each designer identifies the critical signals and ensures their integrity is not compromised.
- Critical signals are supported by analysis, modeling, or technical rationale justifying why they are expected to work.
- Identified critical signals receive special layout attention assuring their proper functioning
- Signal Integrity analysis, test results, and scope pictures should be available at the final design review

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Signal integrity (SI) issue

✓ Signal Integrity (SI) Issue

- Crosstalk
- Charge sharing
- Supply noise
- Leakage
- Propagated noise
- Overshoot
- Under shoot

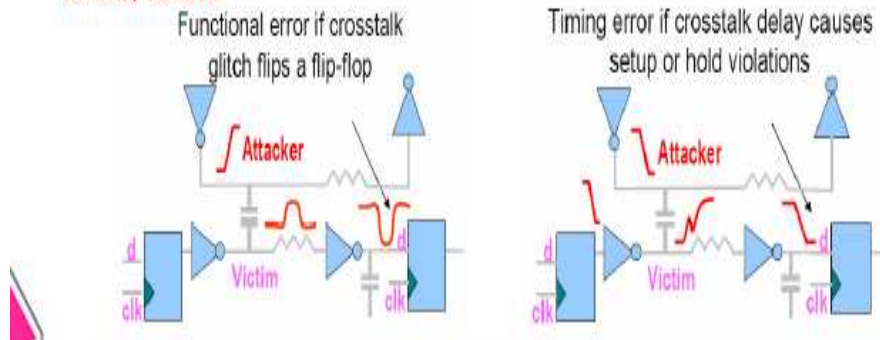


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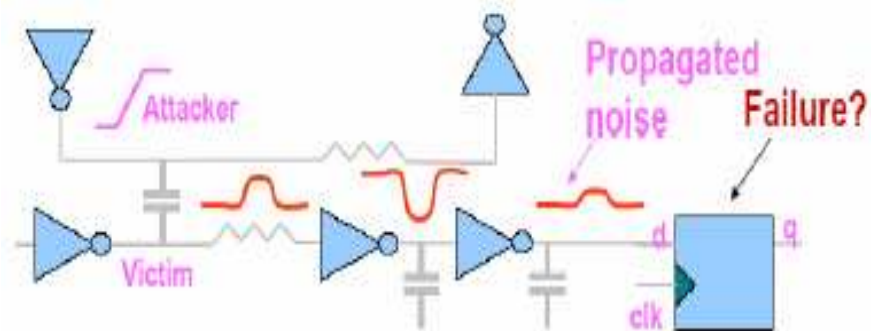
SI Closure

SI closure

- Occur when a design is free from SI induced functional glitch and timing failure

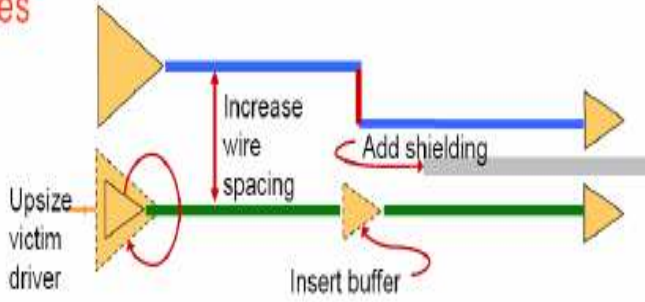


SI analysis



SI Prevention Techniques

SI repair techniques



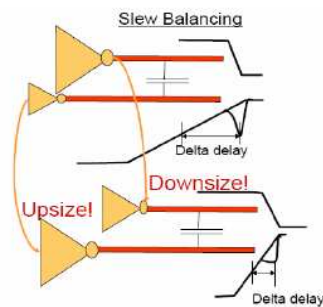
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Signal Integrity Prevention ₁

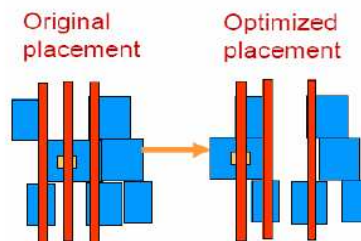
SI prevention

– Placement-based SI prevention

- Reduce crosstalk glitch and delay variation



- Reduce coupling capacitance



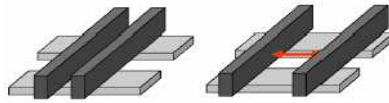
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Signal Integrity Prevention 2

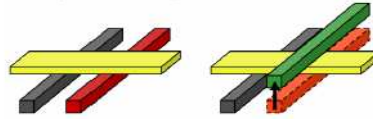
SI prevention (cont.)

- Routing-based SI prevention

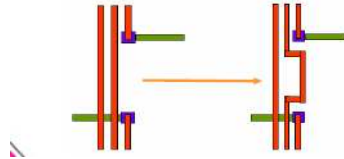
• Wiring Spacing



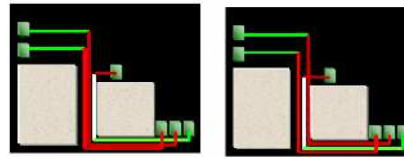
• Layer Switching



• Parallel Wires Reducing



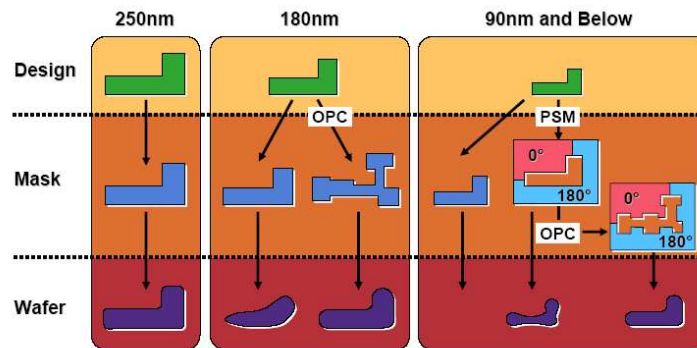
• Net Re-ordering



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Mask producing

Mask optimization



Wavelength: 248nm

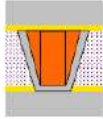
RET: Resolution Enhancement Techniques

OPC: Optical Proximity Correction

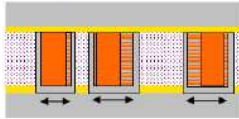
PSM: Phase Shift Mask

Conductors

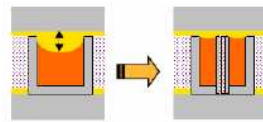
- Non-Rectangular



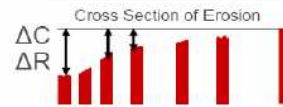
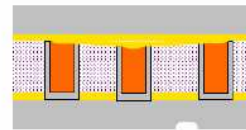
- Wire-Edge



- Dishing, slotting



- Erosion



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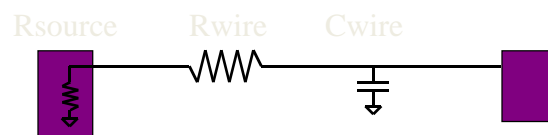
Crosstalk Prevention Strategies ₁

- Placement phase

- Don't know adjacencies, layer assignment, or global route
- Do know net length, est. wire R/C, driver strength, signal slews
- Metrics tell if a net is likely to have problems
- Fixes (size driver, buffer signal) cause no convergence problems

- Global route phase

- Don't know adjacencies, only congestion figure
- Do know layer assignments, better R/C estimates



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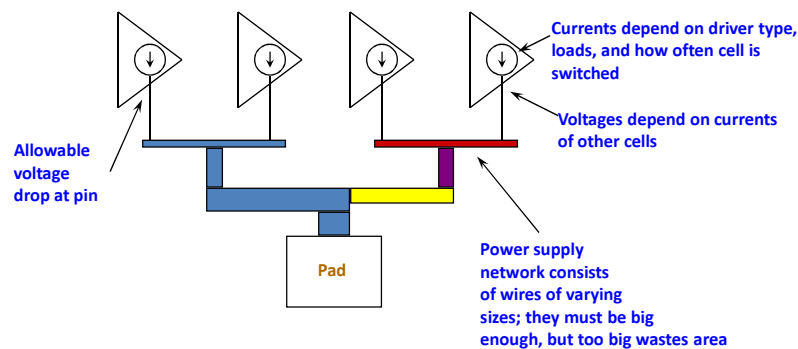
Crosstalk Prevention Strategies

- **Can apply timing windows**
 - only consider signals that can change at the same time
 - data comes from static timing analysis
- **Detailed routing** - detailed analysis and routing ECOs
- N.B.: **In any case**, SI brings potential huge infrastructure changes (e.g., statistical centering design w/distributions)

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IR Drop

- Voltage drop in supply lines from currents drawn by cells
- **Symptom:** chip malfunctions on certain vectors
- **Biggest problem:** what's the worst-case vector?



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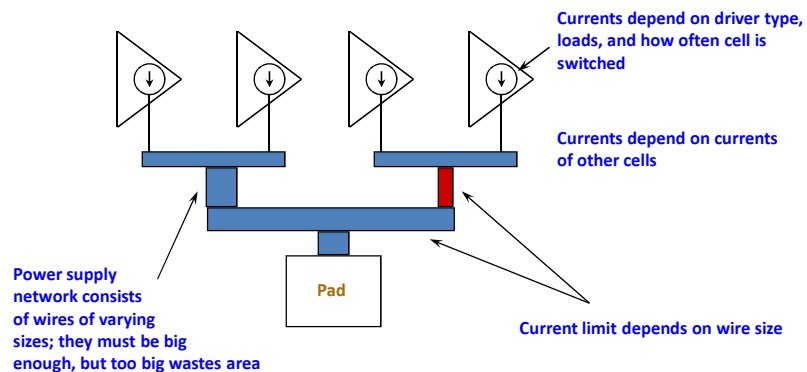
IR Drop

- Analysis
 - model I/O P/G supply; C extraction must distinguish decoupling cap between P/G and coupling cap between signals, P/G
- Prevention (good design)
 - P/G lines on same layer, close to each other; large decoupling on chip; process solutions (e.g., DEC Alpha)

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Electromigration

- Power supply lines fail due to excessive current
- Symptom: chip eventually fails in the field when wire breaks



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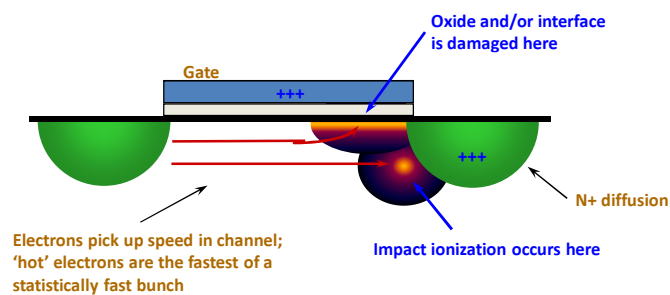
Electromigration

- **Prevention: wire cross-section to current rules**
- **Maximum current density for particular material (via, layer)**
- **Modified Black's equation; waveform models**
- **Higher limits for short, thin wires due to grain effects**
- **Copper: 100x resistance to EM → not a problem any more? (actually, 4-5x)**

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Hot Electron Effects

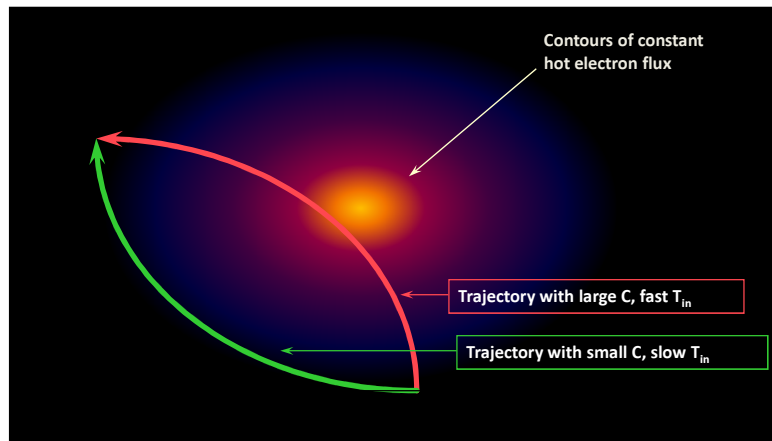
- May also be called short channel effect
- Caused by extremely high electric fields in the channel
 - Occurs when voltages are not scaled as fast as dimensions
- Effect becomes worse as devices are turned on harder
- Symptom: Thresholds shift over time until chip fails



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Hot Electron Effect (cont)

- Depends on how hard device is driven (input slew rate)
- And on the size of the load



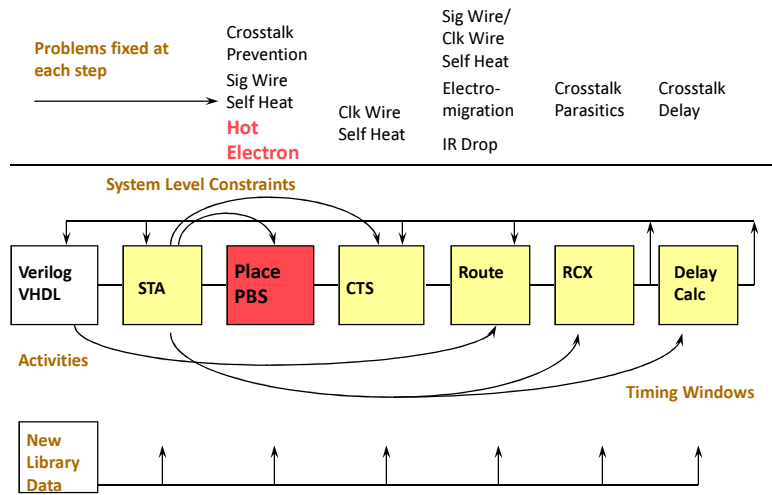
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Hot Electron Prevention Strategies

- Allowable region for input slew and output load
- Fluence per transition is function of input slew, output load
- Set maximum allowed degradation over life of device (estimate of total number of transitions) \equiv fluence limit
- Size device as needed
- Output load vs. driver sizes

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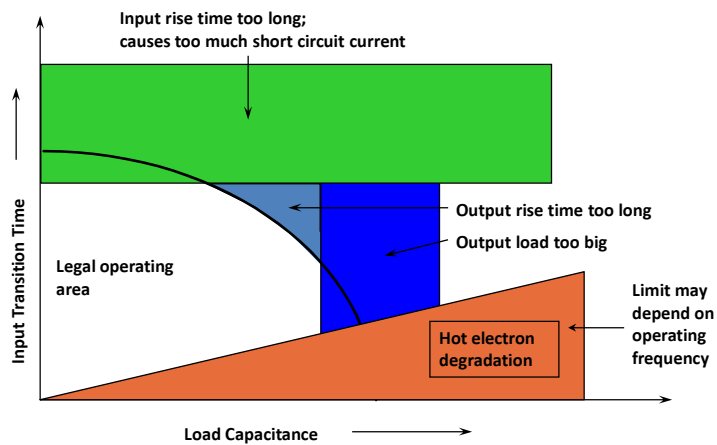
SI Flow - Hot Electron



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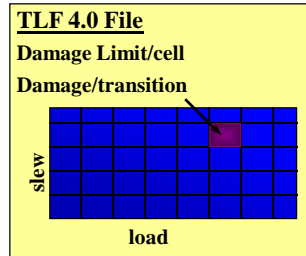
New Design Rule for Hot Electron Effects

- Allowable region for input slew and output load



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Hot Electron Characterization



$$\text{Total fluence} = \text{fluence/transition} * \text{freq} * \text{lifetime}$$

- Get raw process degradation
- Select cell EOL performance (5% timing loss over life)
- Use BTA BERT model to compute total acceptable fluence
- Compute fluence per transition as a function(load, slew)
- Compute Total fluence
- Replace Driver, as needed

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Wire Self-Heat

- May also be called signal wire electromigration
- Wire heats above oxide temperature as pulses go through
- Symptom: chip eventually fails when wire breaks
- Depends on metal composition, signal frequency, wire sizes, slew rates, and amount of capacitance driven
- Requires different data/formulas from power supply EM

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